

SPECIFICATION AMENDMENTS

Please replace the paragraph beginning at page 12, line 3,  
with the following amended paragraph:

~~The drawing figure~~ Fig. 1 is a flowchart of an exemplary  
embodiment of a method for adjusting a substrate in an  
exposure appliance used for transferring a structure to  
the substrate; and

Fig. 2 is a block diagram of an exposure appliance.

Please replace the paragraph beginning at page 12, line 8,  
with the following amended paragraph:

Referring now to ~~the sole drawing figure~~ Fig. 1, there  
is shown a flowchart illustrating one exemplary  
embodiment of the invention. First of all, a map (Step  
10) is to be produced of the unevennesses of a chuck, in  
a lithographic projection appliance. This is done by  
determining the discrepancies between the surface and an  
idealized plane. The exposure or projection appliance  
has a set of focus/tilt sensors, in each case comprising  
a laser and a detector, for example a PSD (Position  
Sensitive Device). The particular tilt as well as the  
particular focus distance can be calculated from a light

beam which is emitted by the laser and is reflected from the surface of a "golden" wafer which is mounted on the chuck.

Please add the following paragraph after line 2 on page 15:

Fig. 2 illustrates an exposure appliance, having a radiation source, a focusing device and a moving chuck.